

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Li-Shun Wang, John Chu

Serial No.: 09/476,633

Filed: December 31, 1999

For: REMOVAL OF RESIDUE FROM A
SUBSTRATE



Art Unit: 2823

Examiner: Garcia, J.

#6/B
10/19/00
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AMENDMENT AND RESPONSE TO OFFICE ACTION

BOX NON-FEE AMENDMENTS
Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In connection with the Office Action mailed on July 5, 2000 regarding the above-referenced Application, the Applicants respectfully request consideration of the following amendments and remarks.

IN THE CLAIMS

Please cancel claim 5.

Please amend the claims as follows:

1. (Twice amended) A method of removing a particle from a metal surface of a via comprising:
introducing a first agent to a metal layer;
polishing the metal layer with the first agent; and